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PATENT APPLICATION

Aug 22 2005

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re United States Patent Application of:)	Docket No.:	ATMI-668 (7493)
Applicants:)	Conf. No.:	4823
Application No.:)	Art Unit:	1752
Date Filed:)	Examiner:	LE, Hoa Van
Title:)	Customer No.:	25559
COMPOSITION AND			
PROCESS FOR POST-ETCH			
REMOVAL OF			
PHOTORESIST AND/OR			
SACRIFICIAL ANTI-			
REFLECTIVE MATERIAL			
DEPOSITED ON A			
SUBSTRATE			

FACSIMILE TRANSMISSION CERTIFICATE**ATTN: Examiner Hoa Van Le****Fax No. (571) 273-8300**

I hereby certify that this document is being filed in the United States Patent and Trademark Office, via facsimile transmission to Mail Stop Amendment, Commissioner for Patents, PO Box 1450, Alexandria, VA 22313-1450, on August 22, 2005 to United States Patent and Trademark Office facsimile transmission number (571) 273-8300.

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Number of Pages


Tristan A. Fuierer

August 22, 2005

Date

**AMENDMENT RESPONDING TO JUNE 2, 2005 OFFICE ACTION
IN UNITED STATES PATENT APPLICATION NO. 10/792,038**

Mail Stop Amendment
Commissioner for Patents
PO Box 1450
Alexandria, VA 22313-1450

08/22/2005 TL0111 000000834 10792038

Sir:

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This responds to the June 2, 2005 Office Action in the above-identified application.

PATENT APPLICATION

Please amend the claims of the application as set out in the following **Section I (Amendments to the Claims)**.

Remarks addressing the substance of the June 2, 2005 Office Action are set out in the **Section II (Remarks)** hereof.